

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	MOS and (nickel adj silicon adj germanium adj silicide)	USPAT	OR	ON	2005/01/10 11:43
L2	263	438/933	USPAT	OR	ON	2005/01/10 11:43
L3	1549	438/197	USPAT	OR	ON	2005/01/10 11:43
L4	1172	438/680	USPAT	OR	ON	2005/01/10 11:43
L5	896	438/682	USPAT	OR	ON	2005/01/10 11:43
L6	1061	438/689	USPAT	OR	ON	2005/01/10 11:44
L7	1805	438/706	USPAT	OR	ON	2005/01/10 11:44
L8	246	438/733	USPAT	OR	ON	2005/01/10 11:44
L9	152	438/752	USPAT	OR	ON	2005/01/10 11:44
L10	677	438/753	USPAT	OR	ON	2005/01/10 11:44
L11	767	438/734	USPAT	OR	ON	2005/01/10 11:44
L12	1509	438/745	USPAT	OR	ON	2005/01/10 11:44
L13	354	438/739	USPAT	OR	ON	2005/01/10 11:45
L14	1	("6653700").PN.	USPAT	OR	OFF	2005/01/10 11:45
L15	1	("6641143").PN.	USPAT	OR	OFF	2005/01/10 11:45
S48	0	MOS and (nickel adj silicon adj germanium adj silicide) and (silicon adj germanium adj alloy)	USPAT	OR	ON	2005/01/10 11:42
S49	0	MOS and (nickel adj silicon adj germanium adj silicide) and (silicon adj germanium adj alloy) and self-aligned	USPAT	OR	ON	2005/01/10 10:17
S50	0	(nickel adj silicon adj germanium adj silicide) and (silicon adj germanium adj alloy) and self-aligned	USPAT	OR	ON	2005/01/10 10:17
S51	0	MOS and (nickel adj silicon adj germanium) and (silicon adj germanium adj alloy)	USPAT	OR	ON	2005/01/10 10:19
S52	18	MOS and nickel and (silicon adj germanium adj alloy) and self-aligned	USPAT	OR	ON	2005/01/10 10:20
S53	18	S52 and (nickel or silicide or silicide or germanium or alloy or undercut or drain or source or region or self or aligned or angstroms or etch or etching or profile or boron or dope or dopant or temperature or concentration or surface)	USPAT	OR	ON	2005/01/10 10:24

1/10/05